

Supporting Information for

## **Transition from Schottky to Ohmic Contacts in 2D Ge/GaAs Heterostructure with High Tunneling Probability**

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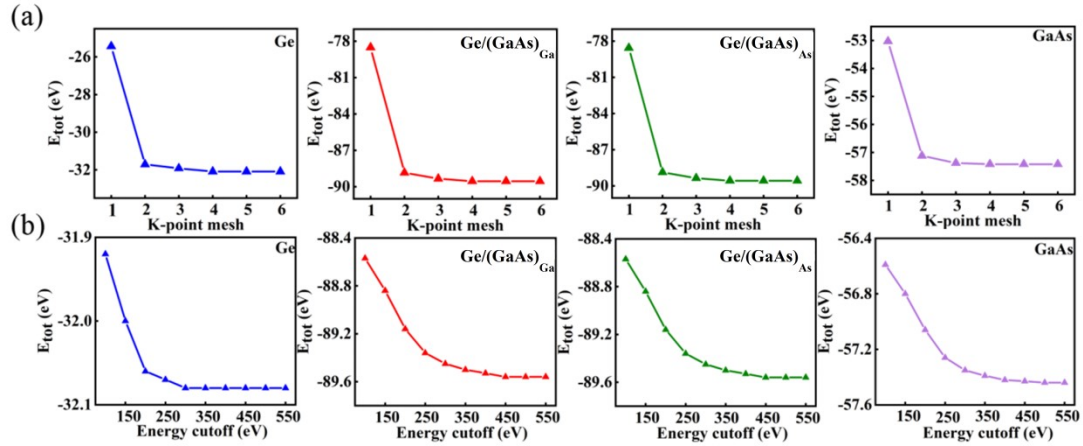
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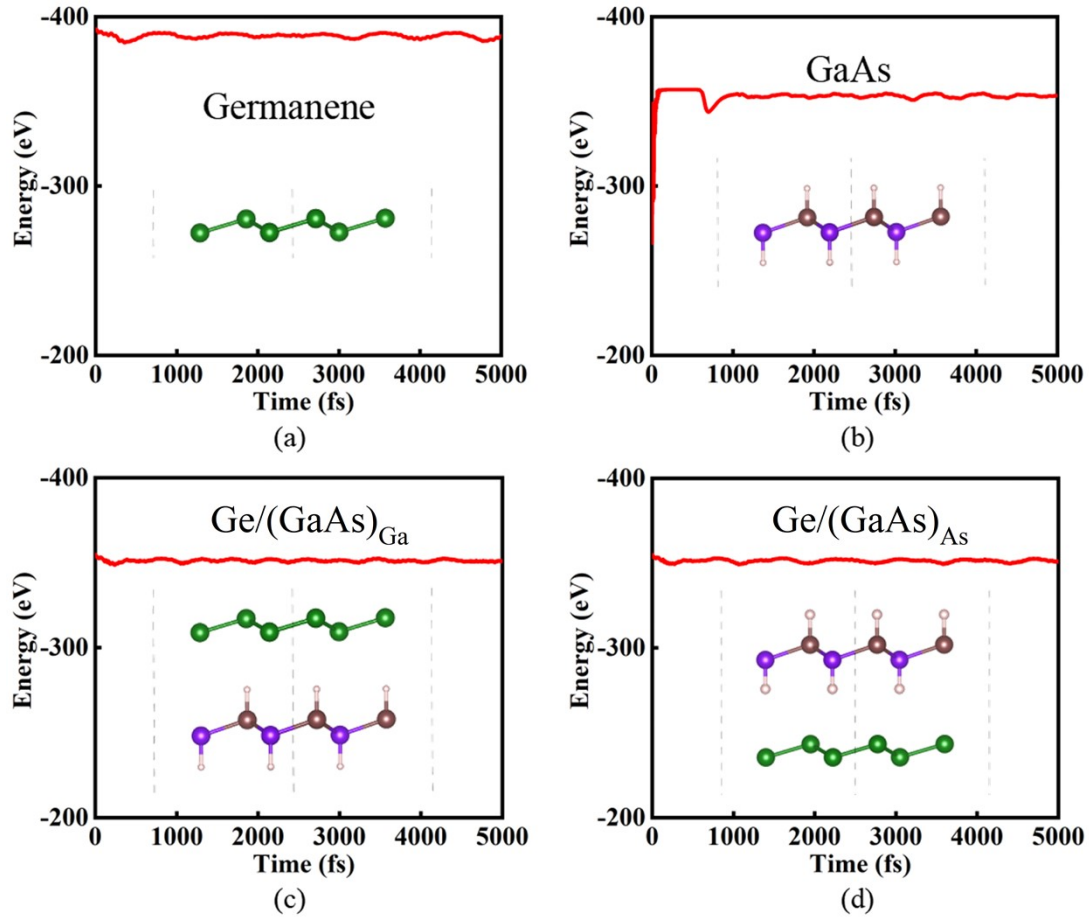
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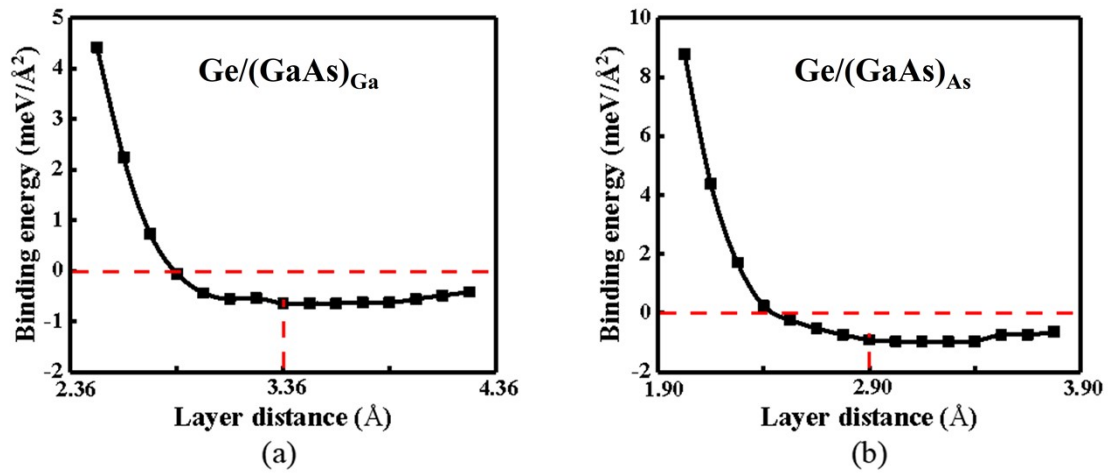
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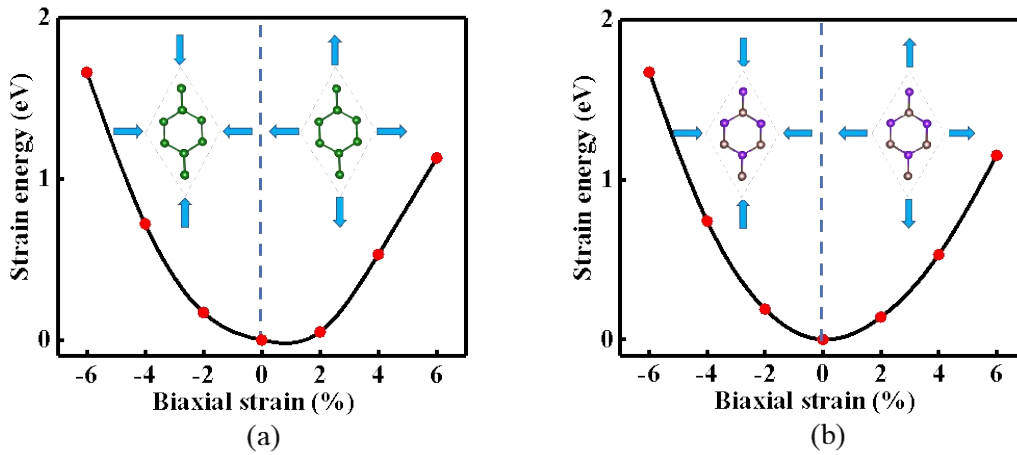
**Fig. S1** The total energies ( $E_{tot}$ ) of Germanene, GaAs monolayer,  $Ge/(GaAs)_{Ga}$  heterostructure, and  $Ge/(GaAs)_{As}$  heterostructure with different k-point mesh (a) and energy cutoff (b).



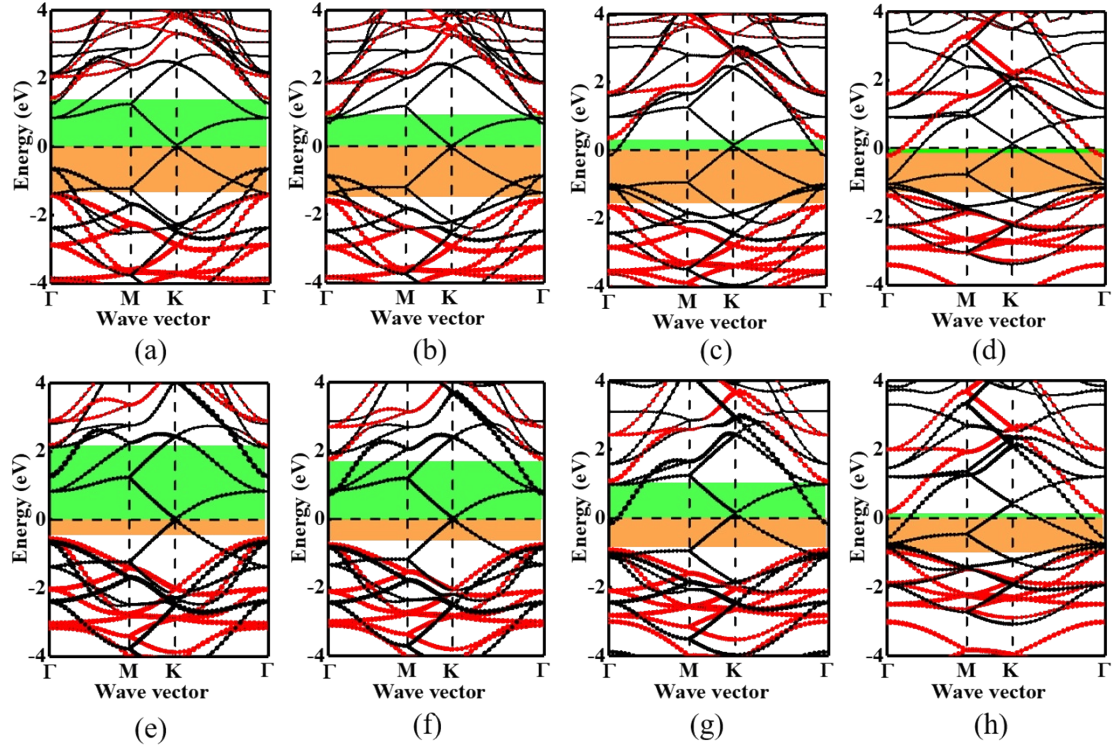
**Fig. S2** The most energetically favorable stacking configuration of (a) Germanene monolayer, (b) GaAs monolayer, (c)  $Ge/(GaAs)_{Ga}$  heterostructure, (d)  $Ge/(GaAs)_{As}$  heterostructure.



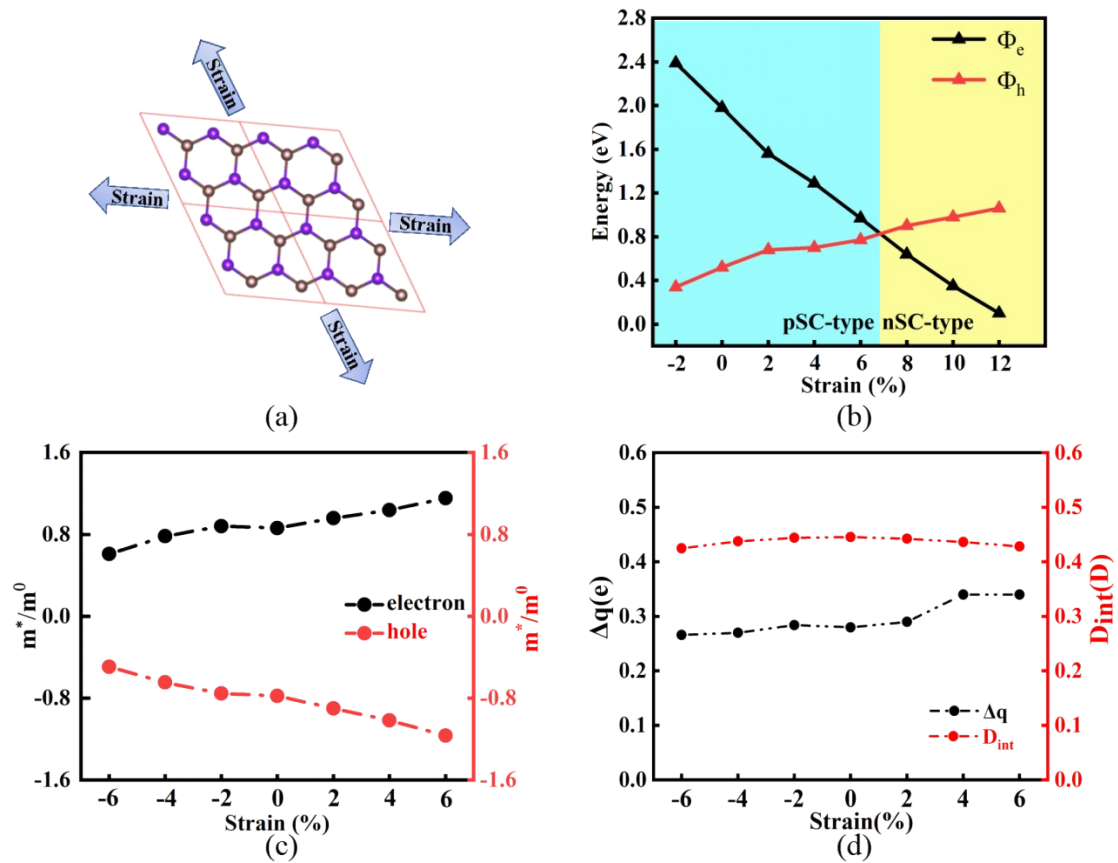
**Fig. S3** The binding energies for Ge/GaAs heterostructures under different layer distance (a) Ge/(GaAs)<sub>Ga</sub> heterostructure, (b) Ge/(GaAs)<sub>As</sub> heterostructure.



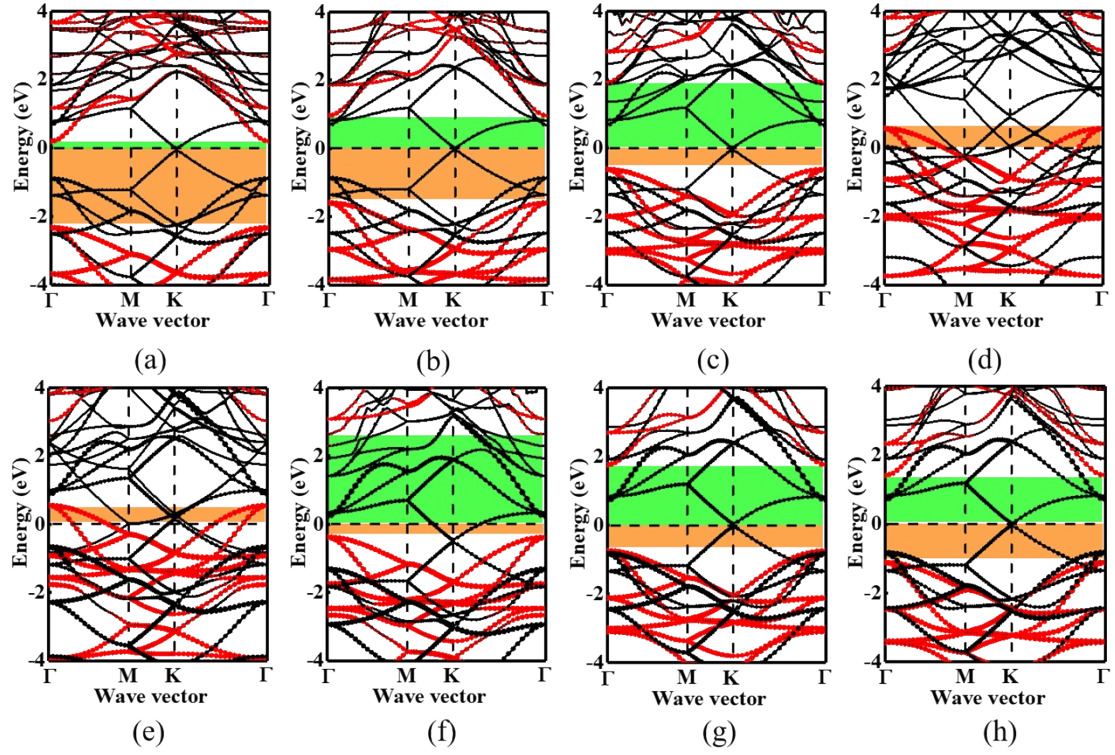
**Fig. S4** The strain energies for Ge/GaAs heterostructures under different biaxial strain (a) Ge/(GaAs)<sub>Ga</sub> heterostructure, (b) Ge/(GaAs)<sub>As</sub> heterostructure.



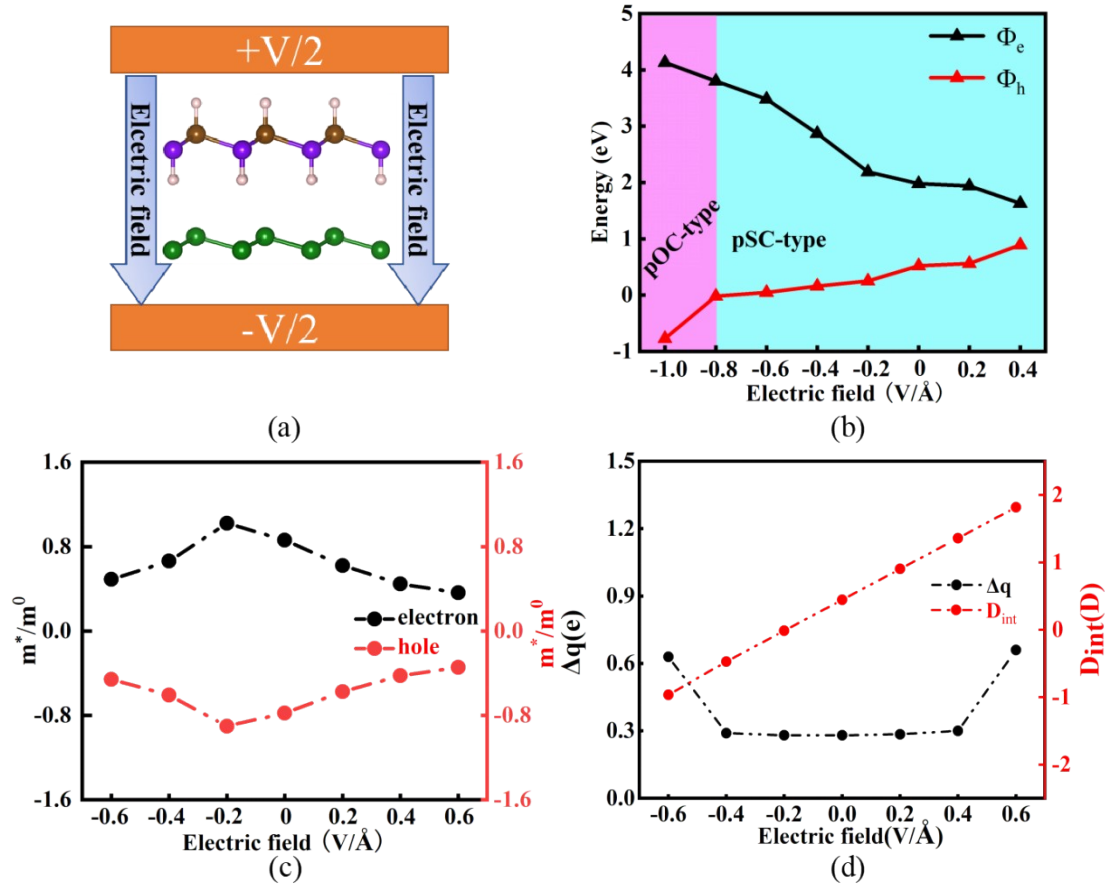
**Fig. S5** The band structure of Ge/(GaAs)<sub>Ga</sub> under (a) -2%, (b)0%, (c)4%, (d)12%, strain, of Ge/(GaAs)<sub>As</sub> under (e) -2%, (f)0%, (g)4%, (h)12% strain. The light green and light brown areas indicate the  $\Phi_e$  and  $\Phi_h$ , respectively.



**Fig. S6** The electronic properties of Ge/(GaAs)<sub>As</sub> heterostructure under different biaxial strain (a) The diagram of tensile biaxial strain, (b) The SBH for electron ( $\Phi_e$ ) and hole ( $\Phi_h$ ), (c) The effective masses of electrons and holes, (d) The charge transfer ( $\Delta q$ ) and interfacial dipole moment ( $D_{int}$ ).



**Fig. S7** The band structure of  $\text{Ge}/(\text{GaAs})_{\text{Ga}}$  under (a)  $-0.2 \text{ (V/\text{\AA})}$ , (b)  $0 \text{ (V/\text{\AA})}$ , (c)  $0.4 \text{ (V/\text{\AA})}$ , (d)  $1 \text{ (V/\text{\AA})}$  electric fields, of  $\text{Ge}/(\text{GaAs})_{\text{As}}$  under (e)  $-0.2 \text{ (V/\text{\AA})}$ , (f)  $0 \text{ (V/\text{\AA})}$ , (g)  $0.4 \text{ (V/\text{\AA})}$ , (h)  $1 \text{ (V/\text{\AA})}$  electric fields. The light green and light brown areas indicate the  $\Phi_e$  and  $\Phi_h$ , respectively.



**Fig. S8** The electronic properties of Ge/(GaAs)<sub>As</sub> heterostructure under different electric fields (a) The diagram of positive electric field, (b) The SBH for electron ( $\Phi_e$ ) and hole ( $\Phi_h$ ), (c) The effective masses of electrons and holes, (d) The charge transfer ( $\Delta q$ ) and interfacial dipole moment ( $D_{int}$ ).

**Table S1** The computed tunneling barrier width ( $W_{TB}$ ), tunneling barrier height ( $H_{TB}$ ), and tunneling probability of carriers ( $P_{TB}$ ) of Ge/GaAs heterostructure under different strain.

<b>Ge/(GaAs)<sub>Ga</sub></b>							
<b>Strain (%)</b>	-6	-4	-2	0	2	4	6
<b><math>W_{TB}</math> (Å)</b>	2.81	2.85	2.89	2.90	2.95	2.96	2.97
<b><math>H_{TB}</math> (eV)</b>	2.43	2.38	2.33	2.26	2.23	2.12	2.05
<b><math>P_{TB}</math> (%)</b>	1.55	1.64	1.73	1.95	1.98	2.39	2.69
<b>Ge/(GaAs)<sub>As</sub></b>							
<b>Strain (%)</b>	-6	-4	-2	0	2	4	6
<b><math>W_{TB}</math> (Å)</b>	1.37	1.42	1.51	1.53	1.46	1.53	1.54
<b><math>H_{TB}</math> (eV)</b>	0.94	0.96	0.98	1.03	0.92	0.91	0.89
<b><math>P_{TB}</math> (%)</b>	32.43	31.01	29.15	27.14	32.05	31.60	32.29

**Table S2** The computed tunneling barrier width ( $W_{TB}$ ), tunneling barrier height ( $H_{TB}$ ), and tunneling probability of carriers ( $P_{TB}$ ) of Ge/GaAs heterostructure under different electric field.

<b>Ge/(GaAs)<sub>Ga</sub></b>							
<b>Electric field (V/Å)</b>	-0.6	-0.4	-0.2	0	0.2	0.4	6
<b><math>W_{TB}</math> (Å)</b>	2.39	2.84	2.87	2.90	2.91	2.93	2.94
<b><math>H_{TB}</math> (eV)</b>	1.98	2.33	2.30	2.26	2.25	2.23	2.21
<b><math>P_{TB}</math> (%)</b>	4.36	1.80	1.85	1.94	1.97	2.01	2.07
<b>Ge/(GaAs)<sub>Ga</sub></b>							
<b>Electric field (V/Å)</b>	-0.6	-0.4	-0.2	0	0.2	0.4	6
<b><math>W_{TB}</math> (Å)</b>	1.67	1.63	1.55	1.53	1.49	1.48	1.50
<b><math>H_{TB}</math> (eV)</b>	1.08	1.05	1.04	1.03	1.03	1.03	1.03
<b><math>P_{TB}</math> (%)</b>	24.0	25.3	26.5	27.1	27.6	27.7	27.5